FORM PTO-1449 (Modified)

## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO.: 170239-00046

SERIAL NO.:10/617,839 APPLICANT: Ji-Guang Zhang FILING DATE: 07/11/03

ART GROUP: EXAMINER: Sheet 1 of 2

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets in necessary)

FR 1.98(b)

U.S. PATENT DOCUMENTS

G					<del>                                     </del>		
Examiner		Document No.	Date	Name	Class	Subclass	Filing Date
Initial	AA	3,237,078	2/66	H.R. Mallory	320	17	3/14/63
7	AB	3,393,355	7/68	P.J. Whoriskey et al	320	18	8/9/65
	AC_	4,154,902	5/79	Schwartz	429	15	9/13/76
	AD	4,303,877	12/81	Meinhold	320	18	5/1/79
	AE	4,614,905	9/86	Petersson et al.	320	18	10/10/83
	AF	4,654,281	3/87	Anderman et al.	429	209	3/24/86
	AG	4,719,401	1/88	Altmejd	320	13	12/4/85
	AH	4,996,129	2/91	Tuck	429	194	12/29/88
			12/93	Hoffman et al.	320	21	2/14/92
	Al	5,270,635	3/94	Feldstein	320	4	9/23/92
	AJ	5,314,765	5/94	Bates	429	194	10/14/93
<b></b>	AK_		8/94	Zuckerbrod et al.	429	252	7/20/93
<b> </b>	AL	5,336,573		Bates et al.	429	193	7/20/92
<b> </b>	AM	5,338,625	8/94		429	249	4/1/93
<b></b>	AN	5,362,581	11/94	Chang et al.	320	18	2/7/92
<u> </u>	AO	5,387,857	2/95	Honda et al.	118	718	6/6/94
<b></b>	AP	5,411,592 5,445,906	5/95 8/95	Ovsbinsky et al. Hobson et al.	429	162	8/3/94
	AQ		10/95	Bates et al.	429	127	5/25/94
	AR	5,455,126	4/96	Bates et al.	204	192.15	5/25/94
-	AS_	5,512,147			429	162	2/25/94
-	AT	5,561,004	10/96	Bates et al.	29	623.5	7/12/94
	AU	5,567,210	10/96	Bates et al.	429	162	6/7/95
	AV	5,569,520	10/96	Bates Corlin et al	429	103	2/22/96
<b> </b>	AW		12/96	Carlin et al.	429	191_	5/25/94
<b> </b>	AX	5,597,660	1/97	Bates et al.			4/17/96
	AY	5,612,152	3/97	Bates	429	152	
	AZ	5,654,084	8/97	Egert	428	215	7/22/94
	ВА	5,778,515	7/98	Menon	28	623.4	4/11/97
	ВВ	5,783,928	7/98	Okamura	320	122	4/2/93
	ВС	5,811,205	9/98	Andrieu et al.	429	137	12/27/95
<b>S</b>	BD	5,821,733	10/98	Turnbull	320	116	12/16/96

EXAMINEN

DATE CONTINERED

Í	Examiner Initial		Document No.	Date	Name	Class	Subclass	Filing Date
0	>V	BE .	5,932,375	8/99	Tarcy et al.	429	231.95	11/19/97
	MG COL	BF	6,071,797 -	6/00	Endo et al.	438	488	9/24/96
/ OCL TO	\$	BG	6,197,450	3/01	Nathan et al.	429	236	10/22/98
OCT 28	DEMIN PL	ВН	6,235,425	5/01	Hanson et al.	429	209	12/12/97

FOREIGN PATENT DOCUMENTS							
ļ	<u> </u>						
		·					
	l						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Journal of Power Sources, P. Fragnaud, R. Nagarajan, D.M. Schleich, D. Vujic, Thin-ΒI film cathodes for secondary lithium batteries, 1995 (M. Aporth) BJ Materials Research Society, The Preparation and Characterization of Lithium Cobalt Oxide Thin Films by LPCVD, 1996 BK Journal of Power Sources, Thin film solid electrolytes and electrodes for rechargeable lithium-ion batteries, J. Schoonman, E.M. Kelder, 1997 (1997) Solid State Ionics, Fabrication of LiCoO2 thin film cathodes for rechargeable lithium BLbattery by electrostatic spray pyrolysis, C.H. Chen et al., 1995 ( NO MONTH) BM Journal of Materials Science, Unique porous LiCoO2 thin layers prepared by electrostatic spray deposition. C.H. Chen et al., 1996 ( A Anna) BN Chemical Congress, Hiroshima, May 1997 BO Materials Research Society, Volume 369, 1995, pages 136-147 BP Reprint from Journal of the Electrochemical Society, Volume 144, No. 2, February 1997 Li-Ion Thin-Film Batteries with Tin and Indium Nitride and Subnitride Anodes MeNx (Me=Sn, In) by B.J. Neudecker and R.A. Zuhr, November 1999 BQ Solid State Ionics 53-26 (1992) 647-654 North Holland, "Electrical properties of amorphous lithium electrolyte thin films" J.B. Bates et al. 

Journal of the Electrochemical Society, 148 (11) A1260-A1265 (2001) "Electrochemical Properties of Carbonaceous Thin Films Prepared by Plasma Chemical Vapor Depostion" Tomokazu Fukutsuka et al. BR-BS

EXAMINER	1100	DATE COMMENTS	9/2./.
CANINGER	WOT	DATE CONSIDERED	7121664

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.